

III-V solar cells research and applications

*John Schermer
Applied Materials Science
Radboud University Nijmegen*

Content

- Wafer-based III-V cells, current status
- How to make better use of the solar spectrum
- Minimizing semiconductor material use
while optimizing individual sub-cell performance
- Summary



Current applications



Spacecraft





Current applications



Concentrated PV
DNI >2400 kWh/m²/yr

Arzon Solar (Amonix)
Alamosa Colorado, 35 MWp
504 Amonix 7700 systems



STACE (Concentrix/Soitec CPV)
Touwsriver, 44 MWp
1500 Soitec CX-S530 II systems



Suncore (Emcore)
Colmud 1&2: 138 MWp
5468 Suncore Gen3.5 systems



What are III-V semiconductors ?



Crystals formed by a 1 to 1 combination of elements from group III and V of the periodic table

I												III		IV	V	VI	VII	VIII		
H 1																			He 2	
Li 3	Be 4											B 5		C 6	N 7	O 8	F 9	Ne 10		
Na 11	Mg 12											Al 13		Si 14	P 15	S 16	Cl 17	Ar 18		
K 19	Ca 20	Sc 21	Ti 22	V 23	Cr 24	Mn 25	Fe 26	Co 27	Ni 28	Cu 29	Zn 30	Ga 31	Ge 32	As 33	Se 34	Br 35	Kr 36			
Rb 37	Sr 38	Y 39	Zr 40	Nb 41	Mo 42	Tc 43	Ru 44	Rh 45	Pd 46	Ag 47	Cd 48	In 49	Sn 50	Sb 51	Te 52	I 53	Xe 54			
Cs 55	Ba 56	La 57	Hf 72	Ta 73	W 74	Re 75	Os 76	Ir 77	Pt 78	Au 79	Hg 80	Tl 81	Pb 82	Bi 83	Po 84	At 85	Rn 86			
Fr 87	Ra 88	Ac 89											III		IV	V	VI	VII	VIII	
												B 5	C 6	N 7						
												Al 13	Si 14	P 15						
												Ga 31	Ge 32	As 33						
												In 49	Sn 50	Sb 51						

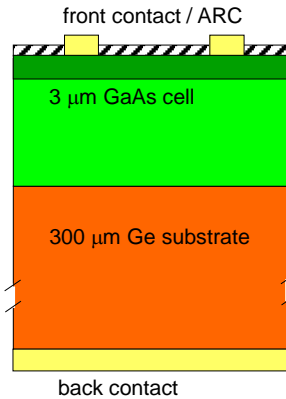
Using the right platform (crystal wafer)

Produce **single crystal films** of 'arbitrary composition'

- materials like: GaAs, InN, AlInP, InGaP, AlGaAsP, etc.
- **tune material properties** by choosing right composition

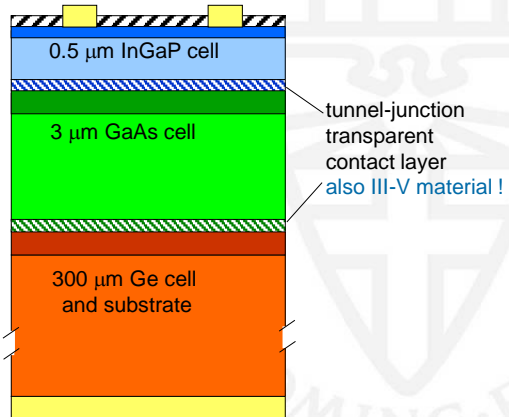
Single junction III-V cell

GaAs (theory: >30%)
 WR: ~~25.1% (Kopin, VS, 1990)~~
26.4% (Radboud 2008)*
27.5% (LG 2015)



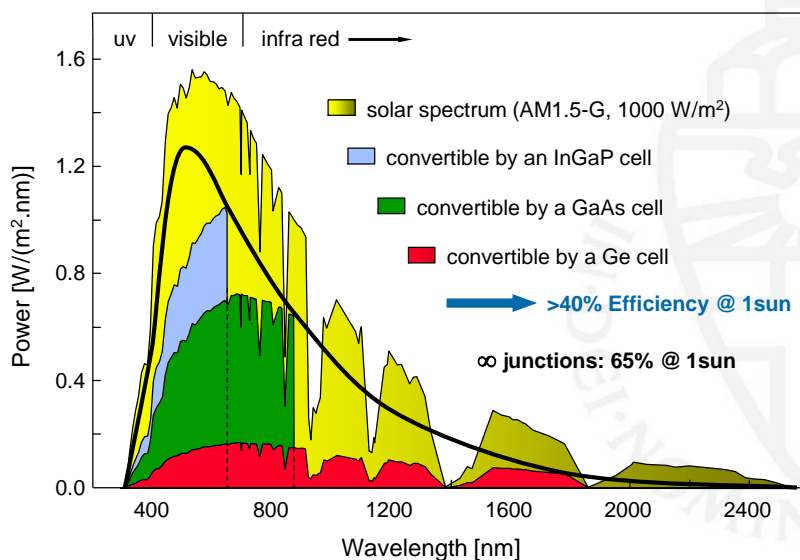
Triple-junction III-V cell

InGaP/GaAs/Ge (theory: >40%)
 WR: 33.2% (ISE-Fraunhofer, 2011)



* Bauhuis et al. Sol. Ener. Mat.&Sol. Cells 93 (2009) 1488

Theory: including V_{oc} and FF diode losses & current matching

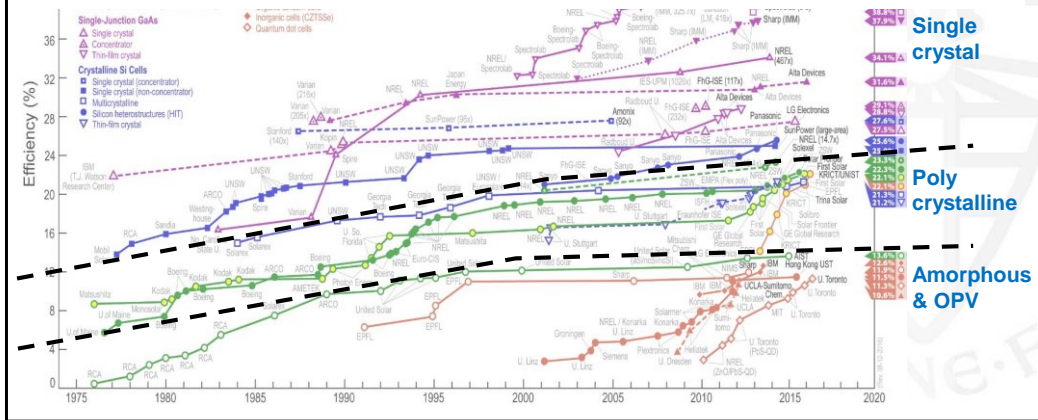


In practice: best research cell efficiencies

Perfect single crystals (low defect density) for high efficiency cells

→ Epitaxial growth on substrate with matching lattice

Which semi-conductors to combine to utilise the entire solar spectrum?

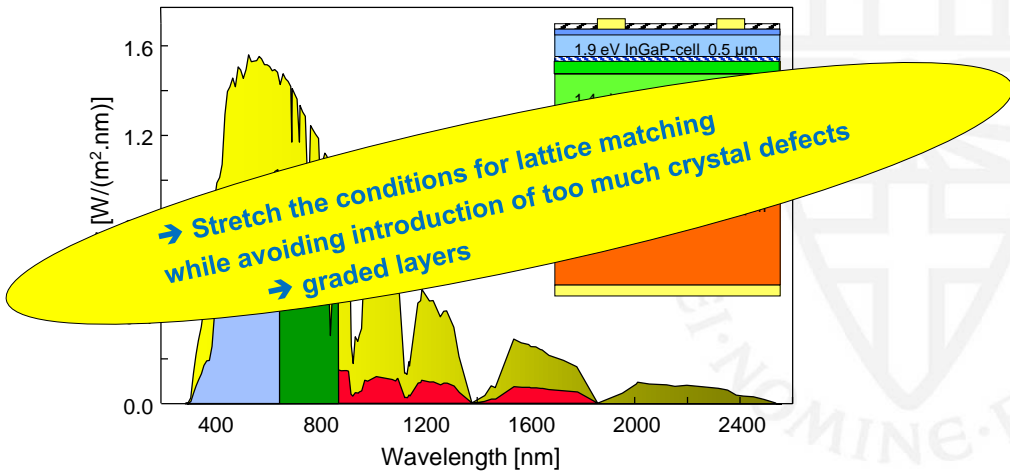


Optimal PV solar energy harvesting

Compared to lattice matched InGaP/GaAs/Ge 3J benchmark

InGaP & GaAs current matched, Ge twice the current

Efficiency ~ 32% @ 1 sun





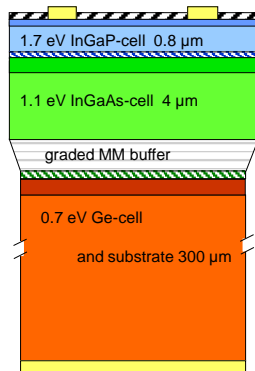
Position the top cells better



Upright MetaMorphic (UMM) cell

Compared to InGaP/GaAs/Ge benchmark

- In \uparrow \rightarrow $V_{oc}\downarrow$ but $J_{sc}\uparrow\uparrow$
- 33.2% @ 1 sun (Fhg-ISE)
- 41.6% @ 364 suns (Boeing Spectrolab)



Position the bottom cell better



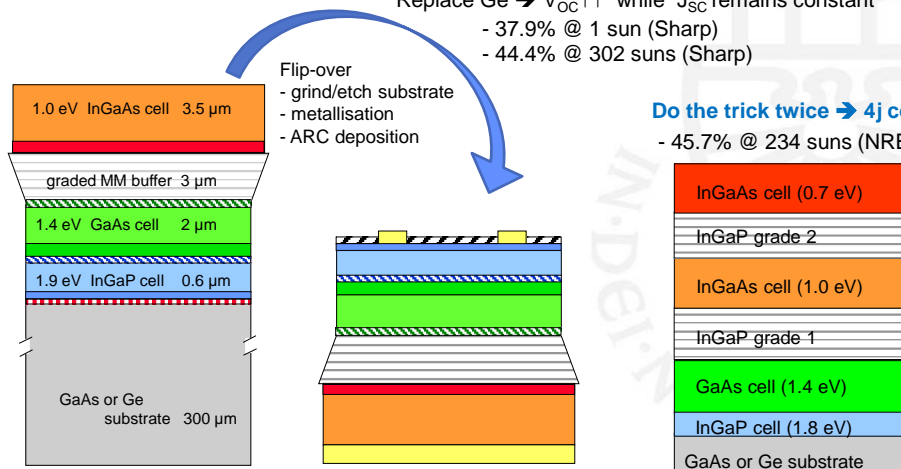
Inverted MetaMorphic (IMM) cell

Compared to InGaP/GaAs/Ge benchmark

- Replace Ge \rightarrow $V_{oc}\uparrow\uparrow$ while J_{sc} remains constant
- 37.9% @ 1 sun (Sharp)
- 44.4% @ 302 suns (Sharp)

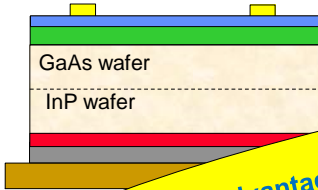
- Flip-over
- grind/etch substrate
- metallisation
- ARC deposition

- Do the trick twice \rightarrow 4j cell
- 45.7% @ 234 suns (NREL)



Wafer bonding type 4J/2 terminal

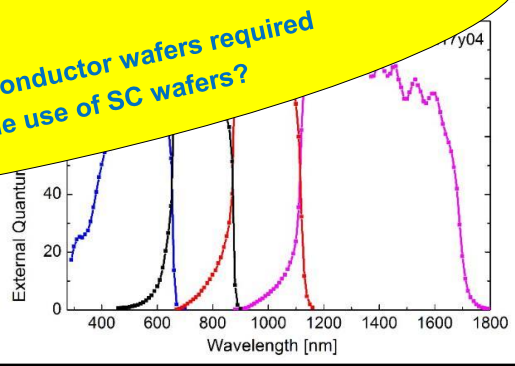
InGaP/GaAs - InGaAsP/InGaAs



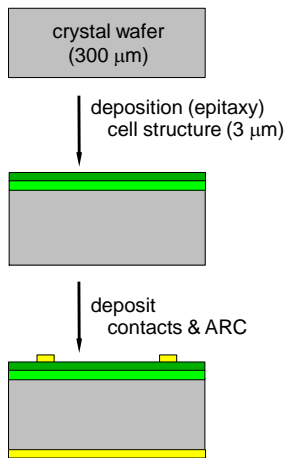
Compared to InGaP/GaAs/Ge benchmark

$V_{oc} \uparrow \uparrow \uparrow$ while J_{sc} remains the same
- 46% @ 508 suns (2000 W/m²)

Major disadvantage
not 1 but 2 precious semiconductor wafers required
→ can we avoid the use of SC wafers?

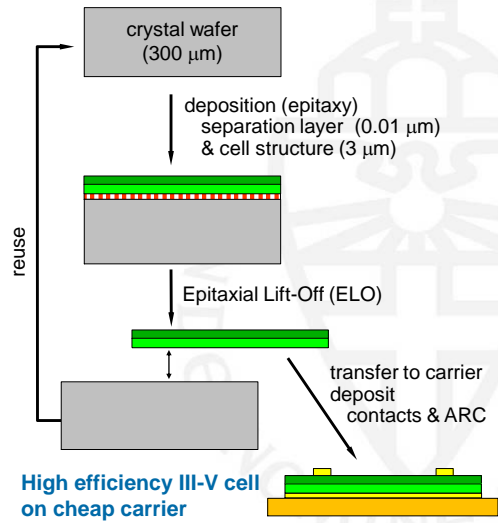


Present production process

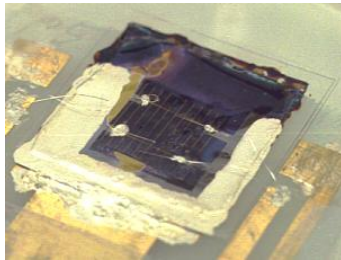


High efficiency III-V cell on expensive wafer

ELO thin-film cell process



High efficiency III-V cell on cheap carrier



1996: first thin-film GaAs cell ($\eta = 10\%$)

Challenge

no "standard" processing technology
thin III-V film and foreign carrier have different properties

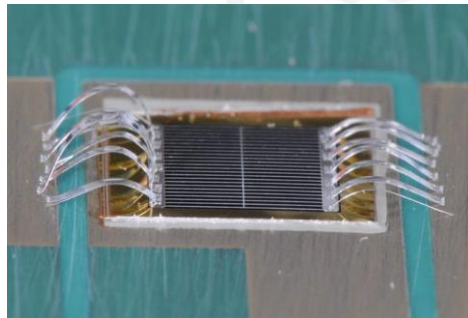
process development & perseverance



World record cell efficiencies

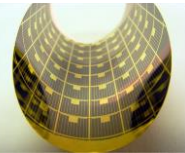
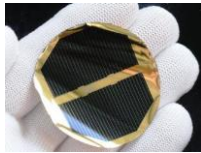
- 2005: 24.5% thin-film cell ($2 \mu\text{m}$)¹⁾
- 2008: 26.1% substrate cell ($3.5 \mu\text{m}$)²⁾
- 2009: 26.1% thin-film cell ($2 \mu\text{m}$)²⁾
- 2011: 28.8% thin-film cell (AltaDevices)
- 2016: 29.3% thin-film cell @ 50 suns (LG)
- 2016: 31.6% thin-film tandem (AltaDevices)

31.7% thin-film tandem @ 300 suns

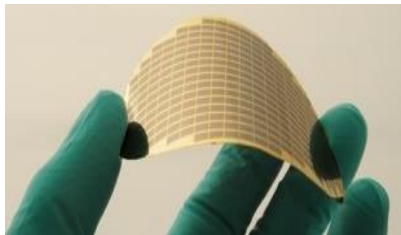


¹⁾ Schermer et al. Thin Sol. Films 511 (2006) 645

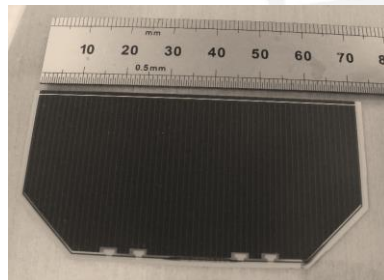
²⁾ Bauhuis et al. Sol. Ener. Mat.&Sol. Cells 93 (2009) 1488



2" epi-film processed
at Radboud University



4" epi-film processed
at spin-out tf2-devices



String of cells
processed from 4" epi-film

Unmanned Aerial Vehicles (UAV)

High-altitude pseudo satellites (HAPS)

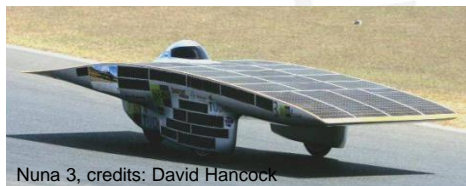


Zephyr T, credits: Airbus

Transport (PV powered cars)

Solar Challenge Australia

- University of Delft/Twente
 - University of Eindhoven / Lightyear
- Producers aiming for III-V
Hanergy & Audi / Toyota



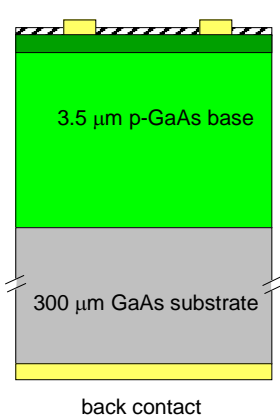
Nuna 3, credits: David Hancock

High-end consumer products

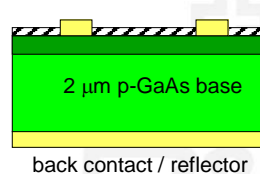
- Laptops
- Smart phones



26.1% wafer based cell



26.1% thin-film cell



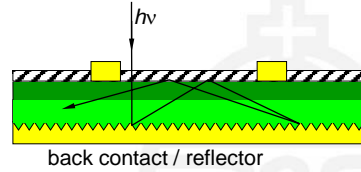
Thin-film vs. substrate-based III-V cells

- less mature thin-film cell processing
- + less SC material required (substrate and epi-layer!)
- + no escape of photons to substrate
→ increased photon recycling
- + low weight, flexible, less heat resistance

Thin-film geometry in principle superior
→ optimisation of the individual junctions

How to maximize this advantage

- 1) Further minimize epilayer thickness
 - increase light-path by surface structuring



- 2) Optimize photon recycling
 - effective increase in light concentration $V_{oc} \uparrow$
 - maximize mirror reflectivity > 90% → more than linear increase in V_{oc} ¹⁾

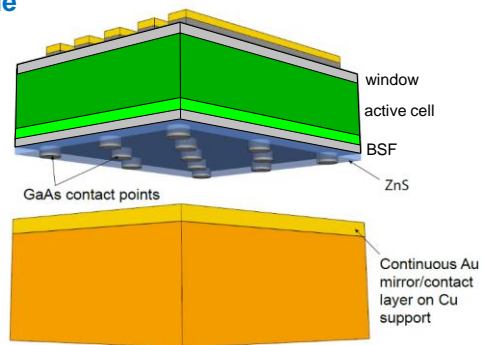
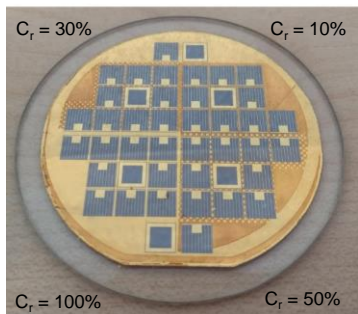
Thin Film cells	V_{oc} [V]	J_{sc} [mA/cm ²]	FF [%]	Efficiency [%]
Radboud University	1.045	29.5	84.6	26.1
Alta Devices WR	1.122	29.68	86.5	28.8

¹⁾ Miller et al., J. Photovolt. 2 (2012) 303

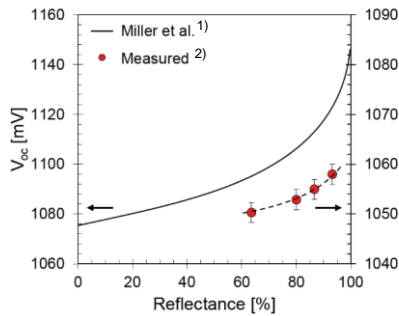
Avoid absorption in highly doped GaAs contact layer ¹⁾

- partly remove back-contact layer → contact points
- fill the gaps with transparent dielectric (ZnS)
- theoretically >30% gain in reflection of reemitted photons

Experimental proof of principle



¹⁾ Gruginskie et al., Thin Solid Films 660 (2018) 10



Onset of theoretically predicted super linear increase of V_{oc} with reflectance

Important note

Gain in V_{oc} only obtained for deep-junction³ thin-film cell
 → cell operates mainly in the radiative recombination regime

¹) Miller, Yablonovitch and Kurtz, J. Photovolt. 2 (2012) 303

²) Gruginskie et al., Thin Solid Films 660 (2018) 10

³) Bauhuis et al., Phys. Stat. Sol. A 231 (2016) 2216

Present III-V cell production (InGaP/GaAs/Ge 3J benchmark)

wafer-based + batch production → high costs

Spacecraft

Concentrator systems in regions with high DNI

- 500-1000x less semi-conductor area & up to 40% cell efficiency
- slow revival, technology from 3 largest producers has passed on



Research

Brute force: apply better fitting or more sub-cells

- step by step extension of CPV to regions with lower DNI
- multifunctional BICPV concepts (start-up companies)



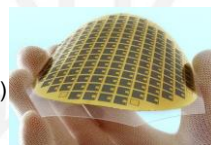
Make the most of each junction

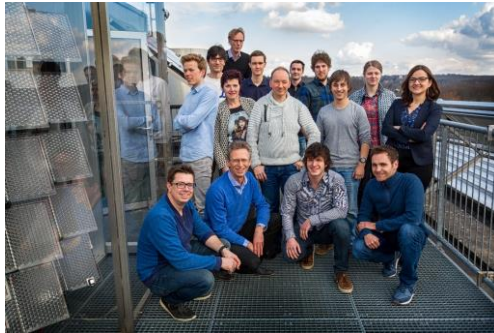
- minimize film cell thickness by maximizing photon confinement photo recycling

Options for cost reduction and additional applications

Wafer reuse (ELO, 100x less semi-conductor thickness)

- flexible, light-weight modules for UAVs & transport (MicroLink, tf2-devices)
- High throughput epi-deposition technology
- >30% flat-plate modules (AltaDevices/Hanergy, LG-electronics)





Staff and students Applied Materials Science group

Cooperative support

ff2 devices	Rera Solutions
Wellsun	SunCycle
CEA/INES	TNO/SEAC
Airbus	Thales Alenia Space
AZUR Space	IMEC
LG Electronics	Tampere University
Politechnic Univ. Turin	Delft University
Umicore	Fraunhofer-ISE
Shell Global Solutions	

**Thank you
for your attention !**

Financial support



Horizon 2020



OPoost
Opportunities for Growth



SEVENTH FRAMEWORK
PROGRAMME



CNPq
SCIENCE
WITHOUT BORDERS



eit RawMaterials
Connecting matters



LG
Life's Good



Rijksoverheid
Rijksdienst voor Ondernemend
Nederland